

SYSTEM, METHOD AND APERTURE FOR OBLIQUE DEPOSITION
ABSTRACT OF THE DISCLOSURE

A deposition system including a shadow mask with one or more apertures, and a method are described for oblique deposition of tilted thin films with azimuthal symmetry. The deposition system is used with physical vapor deposition processes to provide improved control of the angle of incidents of the flux combined with rotation of the substrate to create titled thin films with improved properties compared to conventional oblique deposition techniques.